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## BIB DATA SHEET

CONFIRMATION NO. 6619

<b>SERIAL NUMBER</b> 10/553,095	<b>FILING or 371(c) DATE</b> 10/13/2005 <b>RULE</b>	<b>CLASS</b> 524	<b>GROUP ART UNIT</b> 4171	<b>ATTORNEY DOCKET NO.</b> 2003JP308		
<b>APPLICANTS</b> Tomoko Aoki, Tokyo, JAPAN; Hiroyuki Aoki, Tokyo, JAPAN; <b>** CONTINUING DATA *****</b> This application is a 371 of PCT/JP04/04078 03/24/2004 <b>** FOREIGN APPLICATIONS *****</b> JAPAN 2003-126381 05/01/2003 <b>** IF REQUIRED, FOREIGN FILING LICENSE GRANTED **</b> 02/12/2007						
Foreign Priority claimed <input checked="" type="checkbox"/> Yes <input type="checkbox"/> No 35 USC 119(a-d) conditions met <input checked="" type="checkbox"/> Yes <input type="checkbox"/> No Verified and Acknowledged <u>/WAYNE K LEUNG/</u> Examiner's Signature		<input type="checkbox"/> Met after Allowance Initials	<b>STATE OR COUNTRY</b> JAPAN	<b>SHEETS DRAWINGS</b> 0	<b>TOTAL CLAIMS</b> 12	<b>INDEPENDENT CLAIMS</b> 1
<b>ADDRESS</b> AZ ELECTRONIC MATERIALS USA CORP. ATTENTION: INDUSTRIAL PROPERTY DEPT. 70 MEISTER AVENUE SOMERVILLE, NJ 08876 UNITED STATES						
<b>TITLE</b> Coating composition, porous silica-based film, method for producing porous silica-based film and semiconductor device						
<b>FILING FEE RECEIVED</b> 900	FEES: Authority has been given in Paper No. _____ to charge/credit DEPOSIT ACCOUNT No. _____ for following:		<input type="checkbox"/> All Fees <input type="checkbox"/> 1.16 Fees (Filing) <input type="checkbox"/> 1.17 Fees (Processing Ext. of time) <input type="checkbox"/> 1.18 Fees (Issue) <input type="checkbox"/> Other _____ <input type="checkbox"/> Credit			